

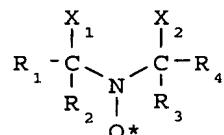
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Amdt. dated March 18, 2005
Reply to Office Action of January 25, 2005

Amendments to the Claims:

Listing of Claims:

1. (Previously Presented) In a process for the production and purification of unsaturated monomers employing distillation means and a nitroxyl-containing polymerization inhibitor of said monomers, wherein a process stream containing the nitroxyl-containing inhibitor is removed downstream of the distillation means and returned to the process ahead of the distillation means, the improvement which comprises recycling said stream containing the nitroxyl-containing inhibitor into the distillation means, wherein the temperature in the distillation means is no higher than about 110° C and the pressure is less than 760 mm Hg.

2. (Original) The process of claim 1 wherein the nitroxyl-containing inhibitor is of the following structural formula:



wherein

R_1 and R_4 are independently selected from the group consisting of hydrogen, alkyl, and heteroatom-substituted alkyl;

R_2 and R_3 are independently selected from the group consisting of alkyl and heteroatom-substituted alkyl; and

X₁ and X₂

(1) are independently selected from the group consisting of halogen, cyano, amido, -S-C₆H₅, carbonyl, alkenyl, alkyl of 1 to 15 carbon atoms, COOR₇, -S-COR₇, and -OCOR₇, wherein R₇ is alkyl or aryl, or

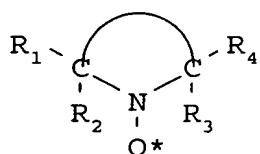
(2) taken together, form a ring structure with the nitrogen.

3 - 8 (Canceled)

9. (Previously Presented) The process of claim 1 wherein the distillation is a continuous operation.

10 - 16 (Canceled)

17. (Original) The process of claim 2 wherein the nitroxyl-containing inhibitor is of the structure



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wherein R₁ and R₄ are independently selected from the group consisting of hydrogen, alkyl, and heteroatom-substituted alkyl and R₂ and R₃ are independently selected from the group consisting of alkyl and heteroatom-substituted alkyl, and the



portion represents the atoms necessary to form a five-, six-, or seven-membered heterocyclic ring.

18. (Original) The process of claim 2 wherein the inhibitor is a blend of two nitroxyls.

19. (Original) The process of claim 17 wherein the inhibitor contains one or more nitroxyls selected from the group consisting of:

N,N-di-*tert*-butylnitroxide;

N,N-di-*tert*-amylnitroxide;

N-*tert*-butyl-2-methyl-1-phenyl-propylnitroxide;

N-*tert*-butyl-1-diethylphosphono-2,2-dimethylpropylnitroxide;

2,2,6,6-tetramethyl-piperidinyloxy;

4-amino-2,2,6,6-tetramethyl-piperidinyloxy;

4-hydroxy-2,2,6,6-tetramethyl-piperidinyloxy;

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4-oxo-2,2,6,6-tetramethyl-piperidinyloxy;
4-dimethylamino-2,2,6,6-tetramethyl-piperidinyloxy;
4-ethanoyloxy-2,2,6,6-tetramethyl-piperidinyloxy;
2,2,5,5-tetramethylpyrrolidinyloxy;
3-amino-2,2,5,5-tetramethylpyrrolidinyloxy;
2,2,4,4-tetramethyl-1-oxa-3-azacyclopentyl-3-oxy;
2,2,4,4-tetramethyl-1-oxa-3-pyrrolinyl-1-oxy-3-carboxylic acid;
2,2,3,3,5,5,6,6-octamethyl-1,4-diazacyclohexyl-1,4-dioxy;
4-bromo-2,2,6,6-tetramethyl-piperidinyloxy;
4-chloro-2,2,6,6-tetramethyl-piperidinyloxy;
4-iodo-2,2,6,6-tetramethyl-piperidinyloxy;
4-fluoro-2,2,6,6-tetramethyl-piperidinyloxy;
4-cyano-2,2,6,6-tetramethyl-piperidinyloxy;
4-carboxy-2,2,6,6-tetramethyl-piperidinyloxy;
4-carbomethoxy-2,2,6,6-tetramethyl-piperidinyloxy;
4-carbethoxy-2,2,6,6-tetramethyl-piperidinyloxy;
4-cyano-4-hydroxy-2,2,6,6-tetramethyl-piperidinyloxy;
4-methyl-2,2,6,6-tetramethyl-piperidinyloxy;
4-carbethoxy-4-hydroxy-2,2,6,6-tetramethyl-piperidinyloxy;
4-hydroxy-4-(1-hydroxypropyl)-2,2,6,6-tetramethyl-piperidinyloxy;
4-methyl-2,2,6,6-tetramethyl-1,2,5,6-tetrahydropyridine -1-oxyl;
4-carboxy-2,2,6,6-tetramethyl-1,2,5,6-tetrahydropyridine -1-oxyl;

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4-carbomethoxy-2,2,6,6-tetramethyl-1,2,5,6-tetrahydropyridine -1-oxyl;

4-carbethoxy-2,2,6,6-tetramethyl-1,2,5,6-tetrahydropyridine -1-oxyl;

4-amino-2,2,6,6-tetramethyl-1,2,5,6-tetrahydropyridine -1-oxyl;

4-amido-2,2,6,6-tetramethyl-1,2,5,6-tetrahydropyridine -1-oxyl;

3,4-diketo-2,2,5,5-tetramethylpyrrolidinyloxy;

3-keto-4-oximino-2,2,5,5-tetramethylpyrrolidinyloxy;

3-keto-4-benzylidine-2,2,5,5-tetramethylpyrrolidinyloxy;

3-keto-4,4-dibromo-2,2,5,5-tetramethylpyrrolidinyloxy;

2,2,3,3,5,5-hexamethylpyrrolidinyloxy;

3-carboximido-2,2,5,5-tetramethylpyrrolidinyloxy;

3-oximino-2,2,5,5-tetramethylpyrrolidinyloxy;

3-hydroxy-2,2,5,5-tetramethylpyrrolidinyloxy;

3-cyano-3-hydroxy-2,2,5,5-tetramethylpyrrolidinyloxy;

3-carbomethoxy-3-hydroxy-2,2,5,5-tetramethylpyrrolidinyloxy;

3-carbethoxy-3-hydroxy-2,2,5,5-tetramethylpyrrolidinyloxy;

2,2,5,5-tetramethyl-3-carboxamido-2,5-dihydropyrrole-1-oxyl;

2,2,5,5-tetramethyl-3-amino-2,5-dihydropyrrole-1-oxyl;

2,2,5,5-tetramethyl-3-carbethoxy-2,5-dihydropyrrole-1-oxyl;

2,2,5,5-tetramethyl-3-cyano-2,5-dihydropyrrole-1-oxyl;

bis(1-oxyl-2,2,6,6-tetramethylpiperidin-4-yl)succinate;

bis(1-oxyl-2,2,6,6-tetramethylpiperidin-4-yl)adipate;

bis(1-oxyl-2,2,6,6-tetramethylpiperidin-4-yl)sebacate;

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bis(1-oxyl-2,2,6,6-tetramethylpiperidin-4-yl)n-butylmalonate;
bis(1-oxyl-2,2,6,6-tetramethylpiperidin-4-yl)phthalate;
bis(1-oxyl-2,2,6,6-tetramethylpiperidin-4-yl)isophthalate;
bis(1-oxyl-2,2,6,6-tetramethylpiperidin-4-yl)terephthalate;
bis(1-oxyl-2,2,6,6-tetramethylpiperidin-4-yl)hexahydroterephthalate;
N,N'-bis(1-oxyl-2,2,6,6-tetramethylpiperidin-4-yl)adipamide;
N-(1-oxyl-2,2,6,6-tetramethylpiperidin-4-yl)-caprolactam;
N-(1-oxyl-2,2,6,6-tetramethylpiperidin-4-yl)-dodecylsuccinimide;
2,4,6-tris-[N-butyl-N-(1-oxyl-2,2,6,6-tetramethylpiperidin-4-yl)]-s-triazine; and
4,4'-ethylenebis(1-oxyl-2,2,6,6-tetramethylpiperazin-3-one).

20. (Previously Presented) The process of claim 1 wherein said monomers contain impurities from the monomer production and/or purification processes.

21. (Previously Presented) The process of claim 20 wherein the impurities include polymer formed during the production and/or purification processes.

22. (Previously Presented) The process of claim 21 wherein the polymer formed during the production and/or purification processes is soluble in the monomer.

23. (Previously Presented) The process of claim 21 wherein the polymer formed during the production and/or purification processes is insoluble in the monomer.

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24. (Previously Presented) The process of claim 21 wherein the equipment in which the distillation process occurs contains polymer.

25. (Previously Presented) The process of claim 24 wherein the polymer was formed during the monomer's production and/or purification processes.

26. (Previously Presented) The process of claim 24 wherein the polymer is not dissolved in the monomer.